



EC4 Equipment Cleaner

DESCRIPTION

EC4 EQUIPMENT CLEANER is a highly concentrated cleaning solution for developing, etching and stripping machines. It will remove a variety of contaminants such as residues from dry film photo resists, solder masks, dyes and anti-foams. A regular maintenance program using EC4 will insure maximum efficiency from equipment with consistent high quality product and minimum down time.

OPERATING PARAMETERS

1. Drain chambers and flush with water 2-3 times. It is important to rinse thoroughly before adding EC4
2. Check for clogged nozzles in both spray and rinse chambers
3. Fill unit with solution of EC4. A concentration of approximately 50% is recommended
4. Allow the solution to circulate for 1-2 hours at room temperature
5. Drain and rinse unit thoroughly (suggested 2-3 times water rinse and drain).
6. Refill unit with either a 5% solution of resist stripper or developer and run for 30 minutes at roughly 120F.
7. Drain and rinse unit thoroughly
8. Replenish chambers with appropriate chemistry.

PHYSICAL PROPERTIES

Specific gravity	1.08-1.20
Appearance	Clear-Amber liquid
pH	<2
Odor	None
Flash Point	>200F

CONTROL PROCEDURES

EC4 solutions can be stored and reused until they no longer clean properly.

ANALYSIS

Not Applicable

SAFETY AND STORAGE

EC4 is acidic and should be handled with care. Avoid open flames Do not store in direct sunlight, high temperature or below freezing.



WASTE TREATMENT

Please ask a Florida CirTech technical sales rep. for more information regarding waste treatment of this chemistry and our complete line of waste treatment line if additional help or information is desired.

MISCELLANEOUS

Packaging comes in 5-gallon pails and 55-gallon drums. Consult MSDS sheet for additional information.